XJP-607A

JP-607A industrial microscope is developed and aimed at the semiconductor industry, wafer manufacturing, electronic information industry, metallurgical industry. Used as an advanced microscope, the user can experience its super performance when using it. It can be widely used to identify and analyze Semiconductor, FPD, Circuit encapsulation, the circuit substrate, Material, Casting/Metal/Ceramic parts, Precision molds and observe thicker specimen. High quality and reliable optical system bring much clearer and contrast image. The design meets the ergonomics needs and makes you feel comfortable and relaxed in doing your job.

Specification		
Viewing Head	Compensation Free Trinocular Head, Inclined 30°（50mm-75mm）	
Eyepiece	WF10×/25mm	
	WF10×/20mm,crosshair with reticule 0.1mm	
Objective	Long working distance Infinite Plan Apochromatic objectives:5×/0.15/W.D.35mm、10×/0.28/W.D.35mm、20×/0.40/W.D.20mm、50×/0.55/W.D.13mm	
Nosepiece	Quadruple nosepiece with center adjustable	
Stage	Double layer mechanical stage	
	Stage Size: 190mm×140mm	
	Moving Range:50mm×40mm	
Filter	Flashboard type Filters:(green,blue,neutral)	
Focusing	Coaxial coarse &fine focusing adjustment with rack and pinion mechanism.Fine focusing scale value 0.002mm	
Light Source	With aperture iris diaphragm and field iris diaphragm, halogen bulb 12V/50W, AC 85V-230V, brightness adjustable	
Polarizing Device	Analyzer rotatable 360,°Polarizer&Analyzer can be moved in/out of the optical path	
Checking Tool	0.01mm Micrometer	
Optional Accessory	Two-dimensional measurement software	
	Professional metallurgical image analysis software	
	Micrometer eyepiece	
	1.3Mega、2.0 Mega、3.0 Mega,5.0 Megapixels CMOS. Digital camera eyepieces	
	Halogen Bulb 12V/100W	
	Precision Stage: X-Y moving range 25mm×25mm, Moving Precision＜5um, Digital handwheel Min.Value:0.1um,360°Rotatable disc	
	Photography attachment and CCD Adapter 0.5×、0.57×、0.75×	
	Objective: 2×	
	Planishing tool	
	CCD Camera,colour 1/3″High resolution 520 TV lines	

Characteristics and description

1.Adopt UIS High-resolution, Long working distance, and infinity light path correcting system objective imaging technology. 2.Extending the multiplexing technology of objective, compatible infinity objective with all the observation methods. 3. Aspherical surface Kohler illumination, increasing the viewing brightness. 4. WF10×（Φ25）super wide viewing field Eyepiece. Micrometer Eyepiece is accessory for a variety of optical measuring instruments, when assembled on an appropriate optical instrument, it can be used for various measurements, such as measuring the holes′distance, width and length of the graduation scale and keyways, metal surface quality, spectrum bandwidth, the density of fiber fabric and the field specimens and so on, it can also measure the size of indentation and scratch as accessory of some microhardness tester.